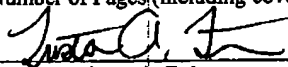


020732-97.668 (7493)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**In re United States Patent Application of:****Applicants: RATH, Melissa K., et al.****Application No.: 10/792,038****Date Filed: March 3, 2004****Title: COMPOSITION AND PROCESS FOR
POST-ETCH REMOVAL OF
PHOTORESIST AND/OR
SACRIFICIAL ANTI-REFLECTIVE
MATERIAL DEPOSITED ON A
SUBSTRATE****) Docket No.: 020732-97.668
(7493)****) Conf. No.: 4823****) Art Unit: 1752****) Examiner: LE, Hoa Van****) Customer No.: 24239****UNOFFICIAL FACSIMILE TRANSMISSION****Attn: Examiner Hoa Van Le****Fax No. (571) 273-1332**

I hereby certify that this document is being filed in the United States Patent and Trademark Office, via facsimile transmission to Examiner Lee's personal facsimile number on October 31, 2006.

31**Number of Pages (including cover)****Tristan A. Fuierer****October 31, 2006****Date****RESUBMISSION OF THE RESPONSE TO AUGUST 30, 2006 OFFICE ACTION IN
UNITED STATES PATENT APPLICATION NO. 10/792,038**

Mail Stop Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to a recent telephone call from Examiner Le, whereby he indicated that the USPTO only received 27 of the 30 pages of the response to the August 30, 2006 Office Action, applicants hereby resubmit said response. Applicants also submit that the original response to the Office Action did include all 30 pages, as indicated in the copy of the Auto-Reply certificate attached herewith in Appendix A.

020732-97.668 (7493)

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the August 30, 2006 Office Action are set out in the **Section II (Remarks)** hereof.